ABSTRACT

PROCESS FOR FORMING DEPOSITED FILM AND PROCESS FOR PRODUCING SEMICONDUCTOR DEVICE

~~A process for forming a deposited film~~ comprises the steps of;

(a) disposing in a space for forming a deposited film a substrate having an electron donative surface;

(b) introducing to the space for forming a deposited film i) a gas comprising an organic metal compound containing a tungsten atom and ii) a hydrogen gas; and

(c) forming a tungsten film on the electron donative surface.

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